

COMPOSITION FOR FORMING METAL-CONTAINING FILM, METHOD OF
PRODUCING COMPOSITION FOR FORMING METAL-CONTAINING FILM,
SEMICONDUCTOR DEVICE, AND METHOD OF PRODUCING SEMICONDUCTOR
DEVICE

ABSTRACT

A composition for forming a metal-containing film, the composition including: a compound (A) which is at least one selected from the group consisting of: a compound (a1) containing a cationic functional group containing at least one of a primary nitrogen atom or a secondary nitrogen atom, and a compound (a2) which is a compound other than the compound (a1) and which contains a nitrogen atom; and a compound (B) which is at least one selected from the group consisting of: a compound (b1) containing a carboxy group and at least one of a germanium atom, a tin atom, a selenium atom or a zirconium atom, and an ester of the compound (b1).

No figure